

**I. General Remarks Concerning This Response**

Claims 1-45 are currently pending. No claims have been amended, added, or canceled in this response. Applicant thanks the examiner for withdrawing the objections to the specification, the objections to the drawings, and the rejection in the previous Office action in view of the previous amendments and response. Applicant also thanks the examiner for discussing the rejection, particularly the Feddele reference, by telephonic interview on multiple occasions.

**II. Summary of Present Invention**

A simple electronic horological device, termed a time cell, is presented with associated methods, systems, and computer program products. A time cell has an insulated, charge storage element that receives an electrostatic charge through its insulating medium, i.e. it is programmed. Over time, the charge storage element then loses the charge through its insulating medium. Given the reduction of the electric potential of the programmed charge storage element at a substantially known discharge rate, and by observing the potential of the programmed charge storage element at a given point in time, an elapsed time period can be determined. Thus, the time cell measures an elapsed time period without a continuous power source. One type of time cell is an analog time cell that may have a form similar to a non-volatile memory cell, particularly a floating gate field effect transistor (FGFET). The time cell may have an expanded floating gate for storing an electrostatic charge. At a given

point in time after programming the analog time cell, a sensing operation indirectly observes the retained charge in the floating gate by directly or indirectly observing the threshold voltage of the FGFET. By knowing the operational characteristics of the time cell and its initial programming condition, the observation can be converted into an elapsed time value. A time cell can be designed and/or programmed to select the range of time to be measured.

10       III. Provisional Nonstatutory Double Patenting Rejection

The Office action has rejected claim 1 under the judicially created doctrine of obviousness-type double patenting as being unpatentable over claim 1 of copending applications 09/703,340, 09/703,334, and 09/703,344. This rejection is traversed.

Applicant disagrees that claim 1 of the present application is obvious over claim 1 of each of the related, co-pending applications. More importantly, the rejection does not provide a proper basis for the obviousness rejection. The rejection states in its entirety:

20       Although the conflicting claims are not identical, they are not patentably distinct from each other because discloses [sic] a time cell, which experiences a transition of states after a programming (charging) 25 operation, detection means for detecting a value within a charge storage element, which is located within the time cell.

The rejection states that the claims are not identical, so a 30 double patenting rejection under 35 U.S.C. § 101 is not appropriate, yet the rejection does not contain a motivational statement as to why one having ordinary skill in the art would

have been motivated to modify any of the claimed structures in the other patent applications to reach the device in claim 1 of the present application. Applicant cannot argue further against the obviousness-type double patenting rejection  
5 without a secondary reference or some other motivational basis against which to argue.

**IV. General Comments Regarding Obviousness Rejections**

Prior to discussing deficiencies in the rejections of individual claims, Applicant presents some initial, general comments concerning each of the obviousness rejections. As a first initial point, the rejections state within multiple statements that a prior art reference or a combination of prior art references teaches a "time cell". In addition, the rejection contains statements as if the term "time cell" was prevalent in the prior art at the time of the present invention, which was not the case. Applicant would like to clarify for the record that a time cell was a novel entity that was disclosed by the present patent application (and its related patent applications). The term "time cell" was coined by the present patent application (and its related patent applications) to distinguish the present invention from prior art memory cells. A patent applicant is allowed to be his/her own lexicographer as long as a term that is used in the claims does not have an art-accepted meaning that significantly differs from the applicant's use of the term and the term is adequately defined in the description. Applicant asserts that the term "time cell" should be given significant deference and consideration.

As a second initial point, each of the obviousness rejections on the independent claims relies on Sakaki (USP 5,500,834) as teaching some aspect of the elements in the claim language. More specifically, the rejections use the  
5 fact that Sakaki teaches the use of a capacitor, and the central argument of each of the rejections is that the use of a capacitor has characteristics that are equivalent to various characteristics of the present invention.

Applicant strongly disagrees with the manner in which the  
10 logic in the rejection is formed and argued. Applicant asserts that the obviousness rejections are deficient because the central argument of the rejections uses an erroneous logical foundation from which to build its reasoning.

Applicant put significant effort into distinguishing the  
15 manner in which the present invention differs from the prior art. Sakaki discloses the discharge of a capacitor through a resistor; its circuit works by discharging the stored charge in a capacitor through a conductive path. The conductive plates or endpoints in a capacitor are directly connected to  
20 conductive leads through which a stored charge flows. In contrast, a time cell in the present invention stores an electrostatic charge in an internal medium of a charge storage element, and the internal medium is substantially surrounded by an insulating medium; there are no conductive leads from  
25 the internal medium to other elements in a system through which stored charge can flow. Hence, the structure of the present invention is significantly different from a conventional RC timer or other circuit that employs a

capacitor, and the method of operation is significantly different from an RC timer or some other circuit.

Applicant also took great care in distinguishing the present invention from the prior art, and Applicant discussed 5 the operation of conventional capacitors in the specification.

In fact, the specification has an entire section, from page 40, line 16, to page 45, lines 11, devoted to distinguishing the present invention from the prior art that one of ordinary skill in the art might mistakenly conclude teaches the present 10 invention. The section at page 41, line 24, to page 42, line 25, was particularly directed to capacitors; it states:

A capacitor can store energy, and a resistor placed 15 in series with the capacitor will control the rate at which it charges or discharges, which produces a characteristic time dependence that can be modeled by an exponential function. The crucial parameter that describes the time dependence is the "time constant" RC. The time constant or RC product of a series circuit determines the speed at which the voltage across a 20 capacitor can change. In industry, circuits combining resistors and capacitors are important because they can be used in timing circuits, signal generators, electrical signal shaping and filtering, and a variety of electronic equipment. However, the discharge times of a capacitor 25 are generally very short, usually on the order of milliseconds but possibly a few hours, even when very large capacitors are combined with very large resistances or impedances.

30 Applicant readily admitted the existence of RC circuits and capacitors, yet the rejections are based on aspects of the operation of capacitors which Applicant has already distinguished.

35 Applicant specifically explained how the present invention is distinguishable from conventional uses of

capacitors, RC circuits, etc.; the most significant portion of the specification states on page 44, line 9, to page 45, line 9 (emphasis added):

5       Moreover, the prior art does not recognize that the discharge process itself is temporally meaningful for most electrostatic storage devices. In the case of the capacitor, in which the prior art does recognize that its discharge rate is temporally meaningful, the capacitor is not entirely insulated and only operates through the use  
10      of conductive contacts. Moreover, an horologically practical application involving a capacitor is only useful because the discharge process then powers other electrical or electronic components with which it has a conductive contact. In fact, capacitors are usually  
15      employed in a manner which cycles the charging and discharging processes in order to achieve some type of electrical time base. Usually called a relaxation oscillator or a relaxation generator, a fundamental frequency can be generated by the time of charging or  
20      discharging a capacitor or coil through a resistor. Hence, capacitors require a continuous power source as they dissipate relatively large amounts of energy for any horological application, which presents a motivating factor for the present invention in which the power  
25      source can be eliminated while the electronic horological device continues measuring time.

30       In contrast to a capacitor, the present invention relies upon a discharge process wherein an electrostatic charge is discharged from an insulated charge storage element over a period of time in such a manner as to allow one to use the discharge process itself as a temporally meaningful process. The manner in which the present invention accomplishes time measurement also allows for common, daily activities over potentially long periods of time.  
35

The statement in this response should not be interpreted as showing the only sections in the specification in which the present invention can be distinguished from the prior art;

there are multiple places within the specification in which the novel aspects of the present invention were emphasized.

In light of the extent to which the specification discusses the differences between the present invention and the prior art and the extent to which the rejections rely on well-known aspects of RC circuits and capacitors, Applicant argues that the central argument of the obviousness rejections appears not to give enough consideration to various novel characteristics of the present invention. Since the central argument in the obviousness rejections is built on an incorrect analogy between the similarities of the present invention and the prior art, generally with respect to conventional capacitors and RC circuits, the obviousness rejections are deficient and improper.

As a third initial point, at least one basis of rejection employs the use of Applicant's "Admitted Prior Art" in the specification concerning non-volatile memory cells. However, Applicant distinguished the present invention from non-volatile memory cells in the specification in the section at page 39, line 31, to page 40, line 14, which states (emphasis added) :

[I]n the prior art, charge leakage from the charge storage elements in non-volatile memory cells was viewed as a detrimental nuisance, and if anything, the prior art taught that charge leakage should be avoided and potentially eliminated. The present invention makes the novel observation that the charge leakage rate can be selected in a manner that allows it to be useful. Using this novel observation, the charge storage element in a non-volatile memory cell can be engineered as an horological device that allows measurements of its operation such that elapsed time periods can be determined. Specifically in this embodiment, as

discussed above, the geometry and physical properties of the insulating medium through which the retained electric charge leaks is selected in a manner which controls the leak rate.

5

Applicant maintains that the prior art teaches away from the novel aspects of the present invention as was originally argued in the specification to prevent the use of admitted prior art from being used in a rejection against the present invention. However, at least one basis of rejection continues to use "Admitted Prior Art" against the claims without providing an argument as to why one of ordinary skill in the art would have been motivated to use the prior art in the manner that is disclosed in the present application.

10

Applicant asserts that a proper rejection needs to provide some independent basis, i.e. prior art, that discloses what is taught in the specification of the present application.

15

Applicant realizes that rejections cannot be discussed abstractly without reference to actual grounds of rejection and actual claim language. Applicant turns now to particular rejections and claims.

V. 35 U.S.C. § 103(a)–Obviousness-Sakaki in view of Feddeler

The Office action has rejected claims 1-17, 24, 25, 25 38-42, 44, and 45 under 35 U.S.C. § 103(a) as unpatentable over Sakaki et al., "Device for measuring time lapse after turn off of power source and method thereof", U.S. Patent 5,500,834, filed 08/28/1994, issued 03/19/1996, in view of Feddeler, "Method and apparatus for performing power on reset initialization in a data processing system", filed 06/01/1992, issued 06/21/1994. This rejection is traversed.

As an initial point, the grounds of rejection do not specifically recite that claim 43 is rejected, but claim 43 is discussed in the Office action in conjunction with the above-noted grounds of rejection.

5       The rejection groups together claims 1-4, 41, 42, 44, and 45. The claim language in these claims is not addressed; instead, the rejection addresses these claims in a general manner based on a description of Sakaki and a description of Feddeler along with an argument as to why one having ordinary 10 skill in the art would have been motivated to combine these teachings. The rejection states: "Sakaki teaches a horological device ..., thereby measuring the electrostatic charge of the capacitor, wherein the above mentioned elements combine to form claimed time cell ...". In other words, the 15 rejection is partially based on a comparison of the present invention with a capacitor in the device of Sakaki. While the rejection provides a fair assessment of the teachings of Sakaki, as noted above, the time cell of the present invention is distinguishable from a capacitor. Hence, Applicant asserts 20 that the obviousness rejection begins with a logically erroneous foundation by comparing the present invention with features in a prior art reference from which Applicant has already distinguished the present invention.

In addition, before the rejection notes the differences 25 between the present invention and the teachings of Sakaki, the rejection states that the features that are disclosed within Sakaki teach the "claimed time cell". In other words, the rejection states that a time cell is taught in Sakaki but then states that certain features of the invention are not taught

in Sakaki. Again, as noted above, the term "time cell" was coined in the present patent application and its related patent applications, and the term "time cell" is disclosed within the specification as comprising many features, 5 including the features that the rejection states are not shown in Sakaki. Applicant asserts that the phrasing of the rejection is inconsistent and clouds the issue as to what features of the present invention are shown in a particular reference.

10 Most importantly, while Applicant asserts above that the rejection builds on a logically faulty foundation, the rejection contains a major mistake with respect to its interpretation of Feddeler. After the discussion of Sakaki, the rejection continues by stating the following about

15 Feddeler:

20 Sakaki does not teach a horological device comprising a floating gate in a floating gate field effect transistor (FGFET), ... Feddeler teaches a data acquisition means that comprising a capacitor that is replaced with a floating gate in a floating gate field effect transistor (FGFET) (col. 4, lines 12+; FIG. 5).

The rejection then provides and discusses a motivational statement for combining the teachings of these sources of 25 prior art.

However, Feddeler does not teach the substitution of a capacitor with a floating gate FET (FGFET); Feddeler teaches the substitution of a capacitor with an insulated gate FET. At column 4, lines 12-25, Feddeler states:

30 FIG. 5 illustrates a circuit 71', which is a different embodiment of circuit 71 of FIG. 4. Circuit 71' differs from circuit 71 in the following manner. In circuit 71', capacitor 62 is replaced by an insulated

gate field effect transistor 69, and capacitor 70 is replaced by an insulated gate field effect transistor 73. Transistors 69 and 73 may be any combination of n-channel depletion mode transistors, p-channel depletion mode transistors, n-channel enhancement mode transistors, and p-channel enhancement mode transistors. In all other respects, circuit 71' is the same as circuit 71. In circuit 71', transistors 69 and 73 each still serve the function of a capacitor.

5

10

15

20

25

30

Feddeler does not mention the use of a floating gate FET nor the substitution of an FGFET for a capacitor. It is possible that the rejection has improperly equated an insulated gate FET with a floating gate FET. Applicant has attached an description or definition of "field-effect transistor" from the "whatis.com" web site that explains that "the MOSFET was originally called the insulated-gate FET (IGFET), but this term is now rarely used." Hence, an insulated gate FET is not a floating gate FET.

In addition, the different types of transistors that are listed in Feddeler refer to the n-type or p-type doping material that is used to form the channel region within a transistor and to the different types of operational characteristics of certain transistors, e.g., depletion-mode ("normally-on") or enhancement-mode ("normally off") transistors. Applicant has attached to this response a set of pages 484-485 from Whitaker, *The Electronics Handbook*, IEEE Press, 01/1996, which describes the different types of metal-oxide-semiconductor field effect transistors (MOSFETs).

The rejection relies on Feddeler as teaching the substitution of an FGFET for a capacitor, but Feddeler does not mention an FGFET. Moreover, Feddeler merely employs the well-known facts that: (1) the operation of a MOSFET can have

significant inherent capacitance that introduces an equivalent capacitor into a circuit; and (2) to achieve certain design advantages or fabrication advantages, a MOSFET might be used in place of a traditional capacitor. Applicant has attached  
5 to this response an article, Cloutier, "Class E AM Transmitters", <http://www.amfone.net/21stAM/classe.htm>, that describes the different type of capacitance that are known to be in effect within a MOSFET. These characteristics are sometimes called "parasitic capacitance" because of their  
10 unwanted effects that degrade the performance of a device that contains a MOSFET.

Hence, Feddele does not teach anything more with respect to the present invention than Sakaki because both references are comparing capacitors with the present invention, and  
15 explained above, Applicant has already distinguished the present invention from traditional capacitors.

With respect to the motivational statement in the main group of claims that is addressed by the rejection, the rejection states: "It would have been obvious to a person skilled in the art at the time of the invention to not only adapt the Sakaki reference and include a floating gate in a floating gate field effect transistor (FGFET) in place of a capacitor ...". Applicant asserts that the rejection is relying on an improper amount of hindsight in arguing that one would have been motivated to use a floating gate FET in place  
20 of a capacitor. Applicant's own specification teaches the novel insight that a floating gate FET can be modified to produce a device that has useful temporal characteristics.  
25 The rejection has not proffered any independent prior art

references that teach or suggest these features. Hence, Applicant's own specification is being improperly employed against Applicant's claimed invention.

Moreover, Applicant argues that one having ordinary skill in the art would not have been motivated to modify Sakaki to include an FGFET. First, as was argued above and in the specification, the prior art teaches away from the present invention; one having ordinary skill in the art would only have regarded an FGFET as being useful for holding a threshold voltage for long periods of time, not for possibly relatively short periods of time. Second, as shown in FIG. 3 of Sakaki, a certain temporal pattern of voltages is desired within the circuit taught by Sakaki, and the effect of holding a charge within an FGFET for long periods of time is opposite to the effect that is desired with a capacitor within the circuit taught by Sakaki. Third, the programming operation for an FGFET is relatively long compared with the charging period of a capacitor; as an example, it is well-known that flash memories that use FGFETs are relatively slow compared to other types of memories, and this slowness is due to the time that is required to program an FGFET or to electrically erase an FGFET. Thus, the programming operation for an FGFET would have introduced an unnecessary and undesired delay into the temporal pattern of voltages that is desired within the circuit taught by Sakaki, thereby changing the principle of operation of Sakaki. Moreover, additional circuitry would be required within the Sakaki device to accomplish the programming operation. MPEP § 2143.01 states the following:

5

If the proposed modification or combination of the prior art would change the principle of operation of the prior art invention being modified, then the teachings of the references are not sufficient to render the claims *prima facie obvious*. *In re Ratti*, 270 F.2d 810, 123 USPQ 349 (CCPA 1959).

10

Applicant asserts that the motivation for combining the references is not logically consistent, and Applicant also asserts that it would not have been obvious to combine the references when doing so requires a change in the principle of operation of the features that are supposedly disclosed in Sakaki, the primary reference.

15

With respect to dependent claims 5-7, which includes the feature in claim 5 of "an array of time cells" and the feature in claim 6 of "wherein at least one time cell in the array of time cells has a predetermined time period that differs from a predetermined time period of another time cell in the array of time cells", the rejection has used a principle from *In re Harza*, 274 F.2d 669, 124 USPQ 378 (CCPA 1960). The rejection states that the claimed features are "mere duplication of parts for a multiplied effect". First, it is unclear what would be meant by a "multiplied effect" in the feature that is claimed in claim 6. Second, Applicant disagrees that the feature is a mere duplication of parts as each time cell in the array could measure a different time period; hence, the time cells would not be duplicates of each other, which the argument in the rejection fails to consider.

20

With respect to claims 8, 9, 24, and 25, which recite various features such as a time cell interface unit and a programming request processing unit, the rejection states that "the combination [of references] does not explicitly comprise

..." but that "any capacitive timing device must inherently possess the structure and means to charge/discharge time cells". First, Applicant argues that the statement in the rejection seems to equate all capacitive timing devices with 5 time cells. As already argued above, the novel term "time cell" was defined in the present patent application, and the term has not been properly interpreted in the rejections, including the rejection of claims 8, 9, 24, and 25. A conventional RC circuit, no matter what its structure is, is 10 not a time cell. Second, the rejection improperly uses an inherency argument by stating: "It would have been obvious to a person skill in the art at the time of the invention to recognize that any capacitive timing device must inherently possess the structure and means to charge/discharge time 15 cells, ...". It is entirely possible for the claimed features to be included in a second device that interfaces with a first device, as described in the specification. Hence, Applicant asserts that the rejection must refer to another reference for these features since they are not found in the prior art 20 references.

With respect to claims 10-13, 38, and 39, which focus on methods of programming and discharging a time cell, the rejection states that "the modified combination of the Sakaki and Feddeler references inherently possess" these methods. 25 Again, Applicant argues that the statement in the rejection seems to equate all capacitive timing devices with time cells. As already argued above, the novel term "time cell" was defined in the present patent application, and the term has not been properly interpreted in the rejections. In addition,

5 this rejection again misuses an inherency argument. As noted above, the rejection does not describe a manner in which one having ordinary skill in the art would have been motivated to combine the cited prior art teachings to reach the claimed devices, so it is not possible for one having ordinary skill in the art to have been motivated to create the methods of using the claimed devices.

10 With respect to claims 14-17 and 40, which focus on a computer program product for using an horological device that comprises a time cell, the rejection merely relies on the rejection of other claims. Applicant maintains that the arguments that were presented above with respect to other claims are also applicable to these claims.

15 With respect to dependent claim 43, which recites that the time cell of the present invention could be used in a smart card, the rejection states that the combination of the prior art references does not disclose this feature, but then the rejection jumps to the conclusion that it would have been obvious to have used the claimed device in a smart card.  
20 Applicant asserts that the rejection improperly uses Applicant's own teachings against the claimed invention.

Examiner bears the burden of establishing a *prima facie* case of obviousness.

25 The examiner bears the burden of establishing a *prima facie* case of obviousness based on the prior art when rejecting claims under 35 U.S.C. § 103. *In re Fritch*, 972 F.2d 1260, 23 U.S.P.Q.2d 1780 (Fed. Cir. 1992). Only when a *prima facie* case of obviousness is established does the burden

shift to the applicant to produce evidence of nonobviousness. *In re Oetiker*, 977 F.2d 1443, 1445, 24 U.S.P.Q.2d 1443, 1444 (Fed. Cir. 1992); *In re Rijckaert*, 9 F.3d 1531, 1532, 28 U.S.P.Q.2d 1955, 1956 (Fed. Cir. 1993). If the Patent Office 5 does not produce a *prima facie* case of unpatentability, then without more the applicant is entitled to grant of a patent. *In re Oetiker*, 977 F.2d 1443, 1445, 24 U.S.P.Q.2d 1443, 1444 (Fed. Cir. 1992); *In re Grabiak*, 769 F.2d 729, 733, 226 U.S.P.Q. 870, 873 (Fed. Cir. 1985). In response to an 10 assertion of obviousness by the Patent Office, the applicant may attack the Patent Office's *prima facie* determination as improperly made out, present objective evidence tending to support a conclusion of nonobviousness, or both. *In re Fritch*, 972 F.2d 1260, 1265, 23 U.S.P.Q.2d 1780, 1783 (Fed. Cir. 1992). 15 With respect to the claims, the rejection argues that a combination of Sakaki and Feddeler discloses the claims, but Applicant has shown above that the prior art, either singly or in combination, does not disclose the claimed features. The rejection also has not properly interpreted terms within the 20 claim language, and the rejection has also incorrectly interprets the teachings of Feddeler. Moreover, the rejection has used logically inconsistent arguments, and in addition, the rejection has improperly used Applicant's own teachings against the claimed invention. Hence, the rejection does not establish a *prima facie* case of obviousness with respect to 25 claims 1-17, 24, 25, 38-42, 44, and 45. Therefore, the rejection of these claims under 35 U.S.C. § 103(a) has been shown to be improper, and these claims are patentable over the

applied reference. Applicant requests the withdrawal of the rejection.

VI. 35 U.S.C. § 103(a)–Obviousness–Sakaki in view of Feddeler and further in view of Applicant's Admitted Prior Art

The Office action has rejected claims 18-23 and 26-37 under 35 U.S.C. § 103(a) as unpatentable over Sakaki in view of Feddeler and further in view of Applicant's "Admitted Prior Art". This rejection is traversed.

The rejection groups together claims 18-23 and 26-31, which are similar to claims 1-4 and 41-45 that were discussed above. Claims 18-23 and 26-31 recite particular structures of a floating gate FET that are not recited within claims 1-4 and 41-45. The rejection of claims 18-23 and 26-21 is similar to the rejection of claims 1-4 and 41-45 except that the rejection relies on the Admitted Prior Art as teaching the structure of an FGFET. Hence, all of the arguments that were provided above against the rejection of claims 1-4 and 41-45 are also applicable to the rejection of claims 18-23 and 26-31.

With respect to claims 32-34 and 36, the rejection states the following (no particular claim is discussed in this rejection as they are grouped together):

[T]he combination of the Sakaki and Feddeler references with the material disclosed in the Admitted Prior Art discloses the claimed invention except for a second source region, a second drain region, a second channel region between the source region and the drain region, and a second control gate. It would have been obvious to one having ordinary skill in the art at the time the invention was made to provide multiple locations of electrostatic discharge in order to increase acquired

data, since it has been held that mere duplication of the essential working parts of a device involves only routine skill in the art. *St. Regis Paper Co. v. Bemis Co.*, 193 USPQ 8.

5

Applicant notes that the claimed elements are not merely duplicated. The rejection has completely overlooked one of the claimed features in independent claim 31 (emphasis added):  
a floating gate, wherein a first portion of the floating gate is between the first control gate and the first channel region and a second portion of the floating gate is between the second control gate and the second channel region;

10

15 A similar structure is present in independent claim 36. The rejection has completely failed to address why this particular structure would have been obvious.

With respect to dependent claim 35, which states that the selected thickness of the tunneling region is less than 7  
20 nanometers, the rejection improperly applies the term "tunneling region" to a typical RC timer circuit. The rejection states: "By applying a typical RC timer circuit characteristics regarding thickness of the insulating region, the electrostatic discharge of a charge storage element can be controlled." The entire argument appears to illogically discuss a tunneling region of a floating gate transistor with respect to capacitive plates in an RC timer circuit; the rejection then jumps to an illogical conclusion. Applicant asserts that the claimed feature is not shown in the prior art  
25 nor could one apply the teachings of one reference to the other in the manner that is described by the rejection.

30

The rejection argues that the prior art discloses some of the claimed features, but Applicant has argued that the prior

art does not disclose certain claimed features. Moreover, the rejection has improperly used hindsight and Applicant's own disclosure against the claim language. Hence, the rejection does not establish a *prima facie* case of obviousness with  
5 respect to claims 18-23, 26-34, 36, and 37. Therefore, the rejection of these claims under 35 U.S.C. § 103(a) has been shown to be improper, and these claims are patentable over the applied references. Applicant requests the withdrawal of the rejection.

Explore the TechTarget Network at [SearchTechTarget.com](http://SearchTechTarget.com).

Activate your FREE membership today | Log-in


[Home](#) [Look It Up](#) [Tech Happenings](#) [Fast References](#) [Job Search](#) [Books & Training](#)
[FREE Conferences >>](#)**Whatis.com Word of the Day:**> [hot site](#) and [cold site](#)**Whatis.com Target Search™**

Search our IT-specific encyclopedia for:

or jump to a topic:

[Advanced Search](#)

Browse alphabetically:

A B C D E F G H I J K L M N O P Q R S T U V W X Y Z #

All Categories → Hardware → Electronics

**field-effect transistor**

EXPLORE THIS AREA: RICH-MEDIA ADVERTISEMENT

See also [bipolar transistor](#) and [transistor](#).

A field-effect transistor (FET) is a type of [transistor](#) commonly used for weak-signal amplification (for example, for amplifying [wireless signals](#)). The device can amplify [analog](#) or [digital signals](#). It can also switch DC or function as an oscillator.

In the FET, current flows along a semiconductor path called the *channel*. At one end of the channel, there is an electrode called the *source*. At the other end of the channel, there is an electrode called the *drain*. The physical diameter of the channel is fixed, but its effective electrical diameter can be varied by the application of a voltage to a control electrode called the *gate*. The conductivity of the FET depends, at any given instant in time, on the electrical diameter of the channel. A small change in gate voltage can cause a large variation in the current from the source to the drain. This is how the FET amplifies signals.

Field-effect transistors exist in two major classifications. These are known as the *junction FET (JFET)* and the *metal-oxide-semiconductor FET (MOSFET)*.

The junction FET has a channel consisting of N-type semiconductor (N-channel) or P-type semiconductor (P-channel) material; the gate is made of the opposite semiconductor type. In P-type material, electric charges are carried mainly in the form of [electron](#) deficiencies called *holes*. In N-type material, the charge carriers are primarily electrons. In a JFET, the junction is the boundary between the channel and the gate. Normally, this P-N junction is reverse-biased (a DC voltage is applied to it) so that no current flows between the channel and the gate. However, under some conditions there is a small current through the junction during part of the input signal cycle.

In the MOSFET, the channel can be either N-type or P-type semiconductor. The gate electrode is a piece of

PAGE 22  
09/703,335

metal whose surface is oxidized. The oxide layer electrically insulates the gate from the channel. For this reason, the MOSFET was originally called the *insulated-gate FET (IGFET)*, but this term is now rarely used. Because the oxide layer acts as a dielectric, there is essentially never any current between the gate and the channel during any part of the signal cycle. This gives the MOSFET an extremely large input impedance. Because the oxide layer is extremely thin, the MOSFET is susceptible to destruction by electrostatic charges. Special precautions are necessary when handling or transporting MOS devices.

The FET has some advantages and some disadvantages relative to the bipolar transistor. Field-effect transistors are preferred for weak-signal work, for example in wireless communications and broadcast receivers. They are also preferred in circuits and systems requiring high impedance. The FET is not, in general, used for high-power amplification, such as is required in large wireless communications and broadcast transmitters.

Field-effect transistors are fabricated onto silicon integrated circuit (IC) chips. A single IC can contain many thousands of FETs, along with other components such as resistors, capacitors, and diodes.

Last updated on: Aug 08, 2000

**What's New**

Learn more about:

> [Introduction to XML](#)

- ⌚ [Site Map for whatis.com](#)
- ⌚ [Our Favorite Technology Blogs](#)
- ⌚ [Quiz #36: Linux basics](#)
- ⌚ [Discussion Forums](#)
- ⌚ [Recently added/updated](#)
- ⌚ [Order the whatis.com book](#)

⌚ Email a friend:

= [Send this page to a friend!](#) [Email a friend](#)

Note: Email addresses will only be used to send site content to your friend(s).

[Home](#) [Look It Up](#) [Tech Happenings](#) [Fast References](#) [Job Search](#) [Books & Training](#)

[About Us](#) | [Contact Us](#) | [For Advertisers](#) | [For Business Partners](#) | [Career Center Contacts](#) | [Awards](#)

Whatis.com is part of the TechTarget network of industry-specific IT Web sites

APPLICATIONS  
[SearchCRM.com](#)  
[SearchSAP.com](#)

CORE TECHNOLOGIES  
[SearchDatabase.com](#)  
[SearchNetworking.com](#)

PLATFORMS  
[Search390.com](#)  
[Search400.com](#)

PAGE 23  
09/703,335

# 37

## Metal-Oxide-Semiconductor Field-Effect Transistor

37.1	Introduction .....	484
37.2	Current-Voltage Characteristics .....	486
	Strong-Inversion Characteristics • Subthreshold Characteristics	
37.3	Important Device Parameters .....	487
	Threshold Voltage • Driving Ability and $I_{D,\text{sat}}$ • Transconductance • Output Resistance and Drain Conductance	
37.4	Limitations on Miniaturization .....	493
	Subthreshold Control • Hot-Electron Effects • Thin Oxides • Dopant-Ion Control • Other Limitations	

John R. Brews  
*The University of Arizona*

### **37.1 Introduction**

The metal-oxide-semiconductor field-effect transistor (MOSFET) is a transistor that uses a control electrode, the gate, to capacitively modulate the conductance of a surface channel joining two end contacts, the source and the drain. The gate is separated from the semiconductor body underlying the gate by a thin *gate insulator*, usually silicon dioxide. The surface channel is formed at the interface between the semiconductor body and the gate insulator, see Fig. 37.1.

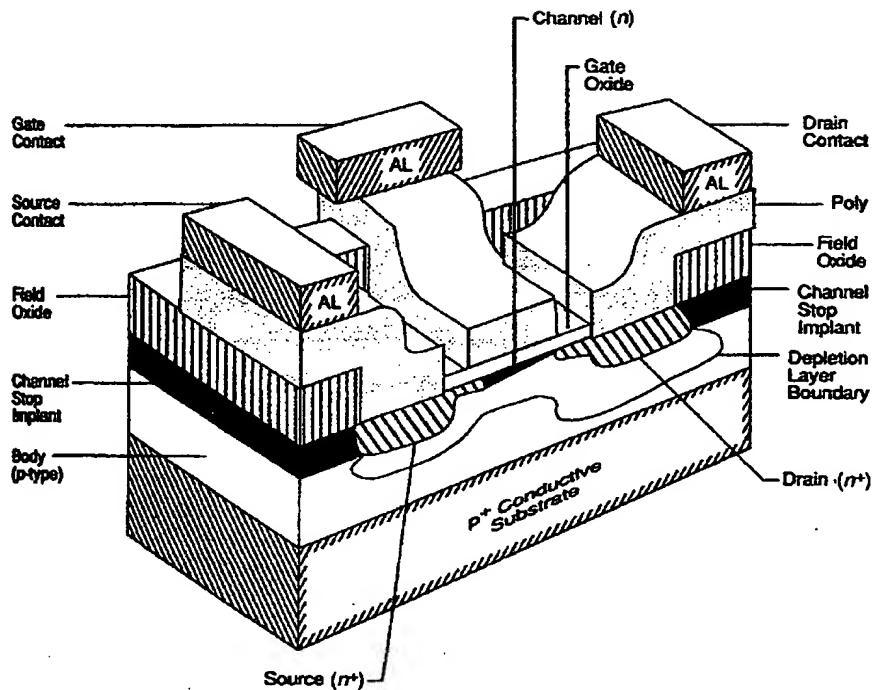
The MOSFET can be understood by contrast with other field-effect devices, like the junction field-effect transistor (JFET) and the metal-semiconductor field-effect transistor (MESFET) [Hollis and Murphy 1990]. These other transistors modulate the conductance of a *majority-carrier* path between two *ohmic* contacts by capacitive control of its cross section. (Majority carriers are those in greatest abundance in field-free semiconductor, electrons in *n*-type material and holes in *p*-type material.) This modulation of the cross section can take place at any point along the length of the channel, and so the gate electrode can be positioned anywhere and need not extend the entire length of the channel.

Analogous to these field-effect devices is the *buried-channel, depletion-mode*, or *normally on* MOSFET, which contains a surface layer of the same doping type as the source and drain (opposite type to the semiconductor body of the device). As a result, it has a built-in or normally on channel from source to drain with a conductance that is reduced when the gate depletes the majority carriers.

In contrast, the true MOSFET is an *enhancement-mode* or *normally off* device. The device is normally off because the body forms *p-n* junctions with both the source and the drain, so no majority-carrier current can flow between them. Instead, *minority-carrier* current can flow, provided minority carriers are available. As discussed later, for gate biases that are sufficiently attractive, above threshold, minority carriers are drawn into a surface channel, forming a conducting path from source to drain. The gate and channel then form two sides of a capacitor separated by the gate insulator. As additional attractive charges are placed on the gate side, the channel side of the capacitor draws a balancing charge of minority carriers from the source and the drain. The more charges on the gate, the more populated the channel, and the larger the conductance. Because the gate creates the channel, to insure electrical continuity the gate must extend over the entire length of the separation between source and drain.

## Metal-Oxide-Semiconductor Field-Effect Transistor

485



**FIGURE 37.1** A high-performance  $n$ -channel MOSFET. The device is isolated from its neighbors by a surrounding thick *field oxide* under which is a heavily doped *channel stop implant* intended to suppress accidental channel formation that could couple the device to its neighbors. The drain contacts are placed over the *field oxide* to reduce the capacitance to the body, a parasitic that slows response times. These structural details are described later. (Source: After Brews, J.R. 1990. The submicron MOSFET. In *High-Speed Semiconductor Devices*, ed. S.M. Sze, pp. 139–210. Wiley, New York.)

The MOSFET channel is created by attraction to the gate and relies on the insulating layer between the channel and the gate to prevent leakage of minority carriers to the gate. As a result, MOSFETs can be made only in material systems that provide very good gate insulators, and the best system known is the silicon–silicon dioxide combination. This requirement for a good gate insulator is not as important for JFETs and MESFETs where the role of the gate is to *push away* majority carriers, rather than to *attract* minority carriers. Thus, in GaAs systems where good insulators are incompatible with other device or fabrication requirements, MESFETs are used.

A more recent development in GaAs systems is the heterostructure field-effect transistor (HFET) [Pearson and Shah 1990] made up of layers of varying compositions of Al, Ga, and As or In, Ga, P, and As. These devices are made using molecular beam epitaxy or by organometallic vapor phase epitaxy, expensive methods still being refined for manufacture. HFETs include a variety of structures, the best known of which is the modulation doped FET (MODFET). HFETs are field-effect devices, not MOSFETs, because the gate simply modulates the carrier density in a pre-existent channel between ohmic contacts. The channel is formed spontaneously, regardless of the quality of the gate insulator, as a condition of equilibrium between the layers, just as a depletion layer is formed in a  $p$ – $n$  junction. The resulting channel is created very near to the gate electrode, resulting in gate control as effective as in a MOSFET.

The silicon-based MOSFET has been successful primarily because the silicon–silicon dioxide system provides a stable interface with low trap densities and because the oxide is impermeable to many environmental contaminants, has a high breakdown strength, and is easy to grow uniformly and reproducibly [Nicollian and Brews 1982]. These attributes allow easy fabrication using lithographic processes, resulting in integrated circuits (ICs) with very small devices, very large device counts, and very high reliability at low cost. Because the importance of

PAGE 25  
09/103, 335

## Class E AM Transmitters

Class E Transmitters are high-efficiency, solid-state transmitters using low-cost standard power MOSFETs. These transmitters are reasonably easy to build, and operate well at frequencies up to *at least* 7 mhz. The frequency limit is constantly being expanded, and this information will be updated as this happens.

An overview of class E operation is presented here. For complete plans, pictures, detailed technical information, schematics, etc. related to class E transmitters, go to [The Official Class E Web Site](#).

## Theory of Operation - The Idea Behind Class E

The idea behind class E is to reduce or eliminate the effects that the capacitances within the FET have on efficiency and operation at high frequencies. The other major operational condition is that the FET is only switched (turned on) when there is no voltage across the device and no current flowing through it. This eliminates switching losses.

There are three capacitances at work within the FET itself; the input capacitance, the output capacitance and the so-called "transfer" (drain to source) capacitance. The effects of the capacitances within the FET are reduced by making the capacitances part of resonant circuits rather than "forcing" energy into and out of the capacitances. Let's look at the various elements.

The element we must consider first, as far as class E operation is concerned is the the drain, or output capacitance. This capacitance exists from drain to source. In normal switching arrangements, this capacitance is simply charged and discharged by the FET(s). However, as the frequency is increased, more and more current is required to quickly charge and discharge this FET capacitance. If this current flows through the FET, the FETs internal resistance will dissipate power. The efficiency will drop dramatically as the frequency is increased. In class E, the output network values are chosen such that the output capacitance is part of a total resonant circuit. The capacitor is "charged" by the flyback effect of the tuned circuit.

The diagram below shows a basic class E RF ouput stage, and the drain and gate voltage waveforms when properly adjusted. The DC voltage applied to the drain in this example is 50Vdc. Notice the peak RF drain voltage rises to almost 200v.

PAGE 26  
09/703, Z35

**VII. Conclusion**

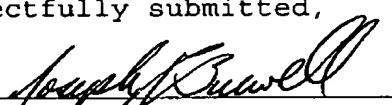
It is respectfully urged that the present application is patentable, and Applicant kindly requests a Notice of Allowance.

5 For any other outstanding matters or issues, the examiner is urged to call or fax the below-listed telephone numbers to expedite the prosecution and examination of this application.

DATE: March 20, 2003

Respectfully submitted,

10

  
Joseph R. Burwell  
Reg. No. 44,468  
ATTORNEY FOR APPLICANT

15

Law Office of Joseph R. Burwell  
P.O. Box 28022  
Austin, Texas 78755  
Voice: 866-728-3688 (866-PATENT8)  
Fax: 866-728-3680 (866-PATENT0)  
Email: joe@burwell.biz

20